Special Issue

Simulation for Analyzing Particle Behavior

Message from the Guest Editor

This Special Issue on "Simulation for Analyzing Particle Behavior" will focus on novel advances in the development and application of computational modeling of analyzing particle behavior. Topics include but are not limited to:

- Development of computational modeling for analyzing particle behavior;
- Measurement of particle behavior and validation; and
- Application of simulation of particle behavior, such as mixing, segregation, chute flow, etc.

Guest Editor

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Deadline for manuscript submissions

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Editor-in-Chief

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